

FACILITATING MINIMUM SPACING AND/OR WIDTH CONTROL DURING OPTICAL PROXIMITY CORRECTION

ABSTRACT

One embodiment of the invention provides a system that facilitates minimum spacing and/or width control during an optical proximity correction operation for a layout of a mask used in manufacturing an integrated circuit. During operation, the system considers a target edge of a first feature on the mask and then identifies a set of interacting edges in proximity to the target edge. Next, the system performs the optical proximity correction operation, wherein performing the optical proximity correction operation involves applying a first edge bias to the target edge to compensate for optical effects in a resulting image of the target edge. While applying the first edge bias to the target edge, the system allocates an available bias between the first edge bias for the target edge and a second edge bias for at least one edge in the set of interacting edges.